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Formation of Nitrogen Oxides by Nanosecond Pulsed Plasma Discharges in Gas-Liquid Reactors

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ABSTRACT

A gas-liquid-film flow reactor with a nanosecond pulsed power supply was utilized to produce nitrogen oxides from Ar/N₂ mixtures (gas phase) and deionized water (liquid phase). Chemical analysis of the stable products found in both the gas and liquid phases was performed and chemical quenching was incorporated for the liquid phase samples in order to eliminate post plasma reactions. Significant amounts of NO and NO₂ in the gas phase and NO₂⁻ and NO₃⁻ in the liquid phase were determined using FTIR spectroscopy and ion chromatography, respectively. The production rate of all nitrogen oxides produced increased significantly with N₂ concentration while H₂O₂ formation decreased slightly. The gas temperature of the plasma was approximately 525 K and was unaffected by N₂ concentration while the electron density ranged from 1x10¹⁷ cm⁻³ in pure Ar to 5.5x10¹⁷ cm⁻³ in 28% N₂. The role of the •OH in the reaction pathway was assessed by adding CO as a gas phase radical scavenger showing that •OH is essential for conversion of the gas phase NO and NO₂ into water soluble NO₂⁻ and NO₃⁻. Conversely, atomic oxygen originating from water is likely responsible for NO and NO₂ generation. Experiments with N₂/O₂/Ar mixtures and air showed a significant increase in NO₂ production caused by the additional generation of reactive oxygen species. An overall energy yield for all nitrogen oxides produced in the most efficient case was 50 eV/molecule.

KEYWORDS

Non-thermal plasma, Nitrogen fixation, Plasma activated water, Nanosecond discharge, Nitrogen oxides

INTRODUCTION

The generation of nitrogen oxides (e.g., NO and NO₂) from N₂ and O₂ in thermal and non-thermal plasma reactors has been extensively investigated over the last approximately 100 years [1-4]. In plasma reactors containing air or mixtures of nitrogen and oxygen, N₂ and O₂ react with plasma generated electrons in a number of different ways including direct dissociation and excitation, and typically the limiting step in the formation of higher oxides of nitrogen is the endothermic formation of nitric oxide, NO [1, 5]. While it has been found that vibrational excitation rather than thermal dissociation of N₂ can lead to a significant increase in the energy efficiency of NO formation, the energy efficiency of NO production with plasma is typically limited by the back reaction of NO with N atoms. Therefore, a quenching step utilizing steep cooling gradients with low pressure non-thermal microwave plasma has led to higher efficiency of NO synthesis from air [1, 6, 7]; however, the cost of such cooling and quenching steps needs further consideration and further oxidation of NO to higher oxides of nitrogen presents additional opportunities for improvements in nitrogen fixation efficiency.

On the other hand, over the last thirty years plasma reactors have also been extensively studied for the removal of nitrogen oxides from combustion and other gases for air pollution control [8-10] through direct and indirect reactions to form liquid soluble products such as nitrite (NO₂⁻) and nitrate (NO₃⁻) [11-25]. In dry gases, the removal of NO from combustion gas involves the oxidation of NO to NO₂, and in both direct and indirect plasma, ozone, O₃, may play an important role in this step [26-28]. The addition of catalysts and utilization of nanosecond pulses have also been found to enhance NO removal from exhaust gases [29-31]. The addition of water to the plasma leads to the formation of hydroxyl radicals (•OH) through water dissociation (and other reactions [32]) and these radicals lead to the formation of NO₂⁻, NO₃⁻, and peroxyxynitrite, ONOO⁻, causing significant decreases in pH due to the formation of the corresponding acids [33-37]. Water can be added in the form of vapor or as a mist, or the plasma can directly touch the liquid phase leading to water evaporating directly into the plasma [38-40]. Such low energy intensive chemical quenching provides an alternative method to produce higher oxides of nitrogen by rapid conversion of NO and NO₂ into products that are quickly absorbed into the liquid where they are less susceptible to degradation by the plasma and where reverse reactions are minimized.

In gas-liquid (argon-water) plasma high efficiency of hydrogen peroxide (H₂O₂) has been demonstrated in a water spray plasma reactor [41, 42] and in a water film reactor [43], and combinations of H₂O₂ and various nitrogen oxides are formed in air and N₂/O₂ plasma contacting water [44]. Since H₂O₂ and NO₃⁻ have very high Henry's Law constants, specifically in comparison to NO and NO₂ [45], under atmospheric conditions the former two species are rapidly absorbed into the liquid phase; although some H₂O₂ exists in the gas no HNO₃ is expected in the gas phase due to the rapid absorption.

Mixtures of such reactive oxygen species (ROS) (e.g., H₂O₂ and •OH) and reactive nitrogen species (RNS) (e.g., NO, NO₂⁻, NO₃⁻, ONOO⁻) formed in plasma reactors with water and air (or mixtures with oxygen and nitrogen) have been termed "plasma activated water" (PAW) and have found recent applications and interests in medicine and agriculture [46-49]. For example, in agriculture the generation of nitrogen oxides with non-thermal plasma has been identified as a promising "green" alternative to the conventional Haber Bosch process [50, 51].

The reaction mechanisms and pathways of plasma nitrogen fixation of dry air and N₂/O₂ mixtures [52] and gas-liquid systems [53, 54] including post plasma reactions [55] have been analyzed through kinetic modeling. Both

experiments and modeling have shown the importance of the post plasma reactions in PAW as well as the key peroxyxynitrite pathway in water [37, 56-58]. While the occurrence of the post-plasma peroxyxynitrite pathway has been proposed as a main reason for the relatively long-lasting antimicrobial properties of PAW, it also significantly complicates chemical analysis of plasma treated liquid water. This is particularly true for distinguishing reactions that occur in the plasma zone versus those that occur in the post-plasma reactions.

The present study utilizes a continuously flowing gas/liquid plasma reactor where the liquid and gas phases exit the system after plasma treatment upon which immediate chemical quenching can be incorporated to eliminate post-plasma reactions in the liquid effluent, and the gas and liquid products can be quickly and directly determined. The gas phase was analyzed using a FTIR flow cell immediately following the plasma reactor and the chemically quenched liquid samples were analyzed with ion chromatography. This work reports the formation of the stable gas and liquid phase products generated by the non-thermal plasma contacting with liquid water with nitrogen present before post-plasma reactions take place to allow for assessment of the products generated by the plasma discharge alone. Mixtures of N_2/Ar and $N_2/Ar/O_2$ were utilized in the feed gas to assess the role of reactive oxygen species versus $\bullet OH$ in the reaction pathway and carbon monoxide (CO) was used as an $\bullet OH$ scavenger to determine gas phase production of this species [59].

EXPERIMENTAL METHODS

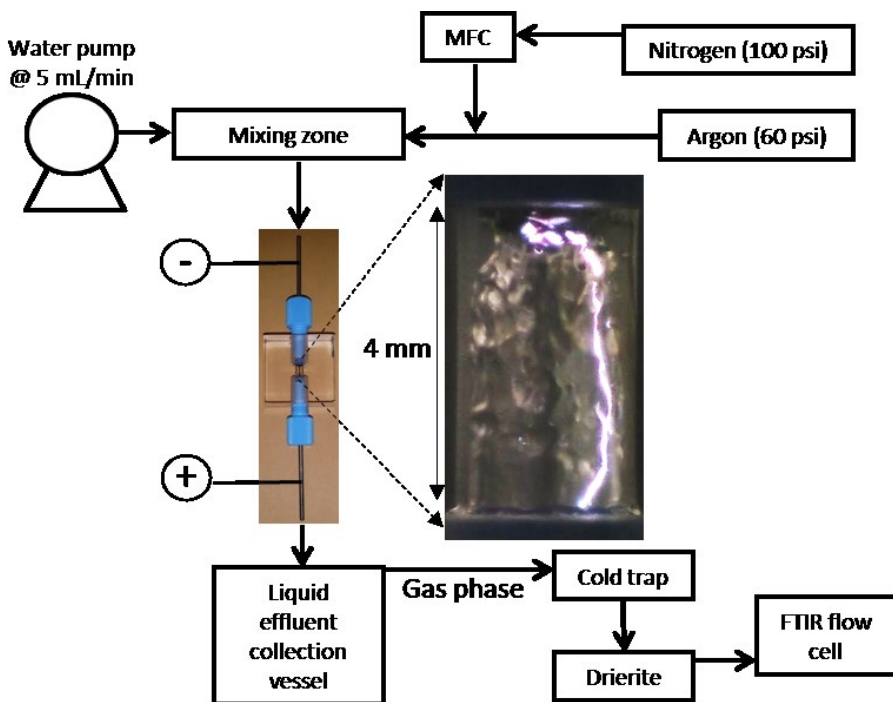


Fig. 1 Process schematic of the experimental setup used in this study. Photo taken at 1/8000 s exposure shows one plasma channel propagating along the gas/liquid interface.

A process schematic for the experimental setup used in this study is shown in Figure 1. Liquid water, delivered at 5 mL/min by a high-pressure reciprocating pump, was mixed with argon (414 kPa, 60 psig) in a mixing

zone (1.6 mm Swagelok tee joint) before entering the inlet of the plasma reactor (0.5 mm ID stainless-steel capillary). The small inner diameter of the inlet capillary limited the total gas flow into the reactor to 3.4 L/min. With this setup the residence times for the liquid and gas were 127 ms and 4 ms, respectively [60]. A mass flow controller (Brooks, 5850E) was used to add N₂ to Ar in order to achieve various N₂/Ar concentrations while maintaining a constant total gas flow rate. A second mass flow controller was employed in experiments where CO or O₂ were added to the N₂ and Ar mixture.

When the gas/liquid mixture enters the discharge region of the reactor a flowing liquid film is formed along the inner walls of the tube and is accompanied by a gas phase flowing through the central core [60]. The stainless-steel inlet and outlet capillaries of the plasma reactor also function as the anode and cathode, respectively. A nanosecond power supply (Eagle Harbor Technologies, Inc.) was connected across the electrodes to produce a filamentary plasma channel which propagates along the interface of the liquid film. The same output settings on the power supply were used for all experiments in this work; 16 kV, 40 ns, 10 kHz. Due to the very short residence times of the gas and liquid phases in the reactor, the reactor quickly reaches steady state after the plasma is turned on. Based on the liquid/gas residence times and the pulse frequency (10 kHz), 1270 pulses occur during the residence time of the liquid (127 ms) while 40 occur for the gas phase (4 ms).

After exiting the plasma reactor, the liquid phase was collected in a sampling vessel while the gas phase flowed directly to an FTIR spectrometer (Jasco - 6700) equipped with a 5 m gas flow cell. Prior to entering the flow cell, the gas phase passed through a dry-ice/acetone cold trap followed by a DIERITE® packed bed to remove remaining water which due to its large dipole moment causes significant interference with the FTIR measurement. For experiments where CO was used, the CO₂ concentration in the gas phase effluent was also quantified using FTIR. More details on the gas phase measurement including sample spectra can be found in the Appendix.

The NO₂⁻ and NO₃⁻ in the liquid phase of the effluent were analyzed using ion chromatography (Dionex, Aquion). Due to the occurrence of post-plasma reactions between H₂O₂ and NO₂⁻, the liquid phase of the effluent was discharged into a solution of NaOH to slow down the reaction rate of the peroxyxynitrite reaction pathway for accurate quantification of the concentrations exiting the reactor [58]. For H₂O₂ measurements, the effluent was discharged into a sodium azide solution to rapidly remove NO₂⁻ from the solution before quantification with the TiSO₄ colorimetric method using a UV-Vis spectrometer (PerkinElmer, Lambda 35) [58, 61]. The conductivity and pH were determined in separate samples without the addition of NaOH or sodium azide. More details on the liquid phase measurement can be found in the Appendix.

Voltage and current were measured with an oscilloscope (Tektronix MDO 3014; Beaverton, OR) equipped with two high voltage probes (TektronixP6015A, 1/1000; Beaverton, OR) in conjunction with a Rogowski coil (Pearson Electronics, model 6585; Palo Alto, CA). Energy per pulse was determined by integrating the instantaneous power ($V \times I$) across the entire pulse as in Equation 1.

$$\text{Energy per pulse} = \int (V \times I) dt \quad \text{E1}$$

V: Instantaneous voltage

I: Instantaneous current

t: Time

The energy yield for chemical species produced was determined by dividing the average discharge power by the rate of production. More details on the electrical measurement including temporal probe alignment can be found in the Appendix as well as in previous publications using the same system [60, 62].

Time averaged electron density and gas temperature of the plasma were estimated using optical emission spectroscopy (Avantes, AvaSpec-ULS3848; wavelength range: 300-403 nm for gas temperature, 600-700 nm for electron density). For N₂ concentrations less than 5%, gas temperature was determined using •OH (A-X) from 305-320 nm using the same method from our previous work, i.e. two temperature fitting of the Boltzmann plot obtained using MassiveOES [62-65]. For higher concentrations of N₂, the gas temperature was determined with the N₂ (C-B) at 337 nm following the fitting protocol in Vorac et al. using MassiveOES [64, 65]. Electron density was estimated using Stark broadening of the H_α peak at 656.3 nm using two-Voigt function. More details of this measurement can be found in the Appendix as well as our previous work [62, 63, 66, 67].

All measurements were repeated in triplicate and the error bars found throughout this manuscript represent plus and minus one standard deviation from the mean.

RESULTS AND DISCUSSION

The focus of this work is chemical species analysis, however, for assessment and comparison of chemical species generation in this plasma system to other plasma and non-plasma processes, measurement of the electrical and plasma properties as well as visual observations of the plasma are essential.

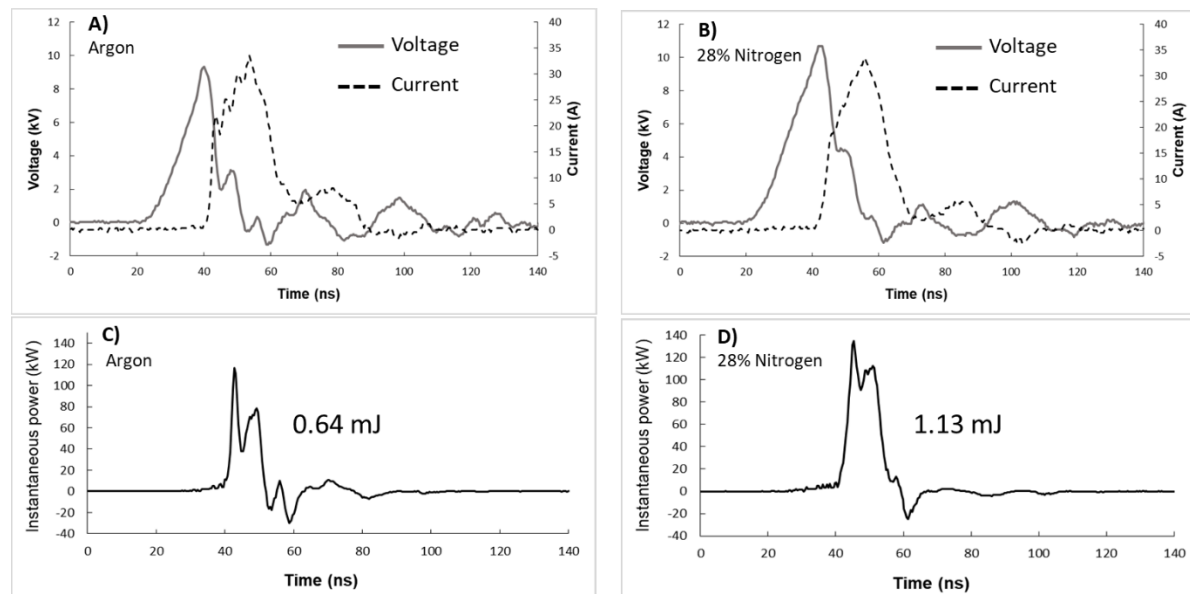


Fig. 2 Voltage and current waveforms (A and B) and instantaneous power (C and D) for pure Ar and 28% N₂

Table 1 Electrical measures for various concentrations of nitrogen in argon

Nitrogen (%)	Energy per pulse (mJ)	Peak voltage (kV)	Peak current (A)	Average discharge power (W)
0.00	0.64	9.83	33.47	6.37
0.06	0.76	9.20	32.40	7.59
0.71	0.75	8.87	32.00	7.48
1.77	0.78	9.61	32.67	7.82
3.55	0.82	9.16	31.87	8.21
7.10	0.84	9.40	32.00	8.39
14.19	1.08	9.83	31.33	10.76
21.29	1.08	10.73	33.07	10.76
28.39	1.13	10.81	33.07	11.35

Figure 2 and Table 1 show the electrical properties of the discharge for various concentrations of N₂ in Ar. At 28% N₂ the total energy dissipated per pulse increased by approximately a factor of 2 when compared to pure Ar. The peak current was unaffected by increasing N₂ and the peak voltage (breakdown voltage) increased by 10%. The increase in breakdown voltage is consistent with Paschen's law where the breakdown voltage for N₂ is higher than argon [68]. The slight increase in breakdown voltage provides one cause of the significant increase in total energy. When the instantaneous powers ($I \cdot V$) for pure Ar and the 28% N₂ mixture are compared (C and D of Figure 2) it also appears that the pulse duration is slightly longer with N₂ added and this also contributes to the higher energy per pulse. No significant changes of the voltage and current were found with the addition of O₂ or CO at the concentrations utilized, 0-15% and 0-5%, respectively.

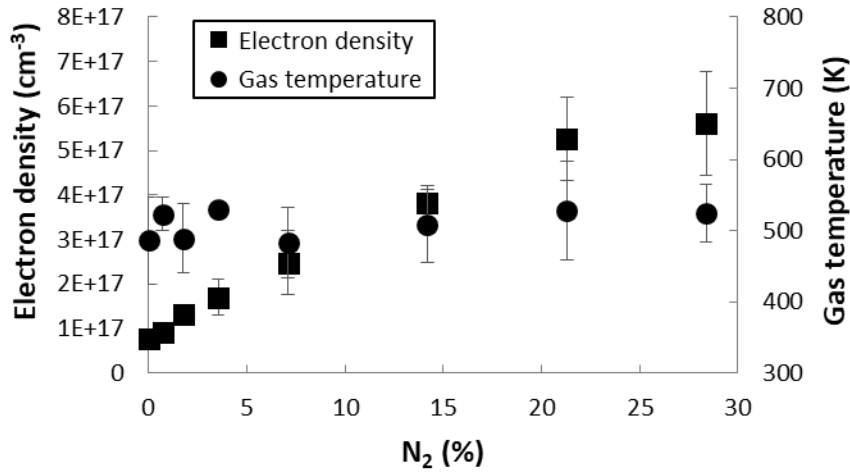


Fig. 3 Gas temperature and electron density as a function of nitrogen concentration

The electron density and gas temperature for the plasma discharge are shown in Figure 3 for various concentrations of N₂ in Ar. The gas temperature was found to be approximately 525 K and was unaffected by the N₂ concentration. A linear increase in electron density was found with increasing N₂ concentration. With no N₂ present the electron density was 1 × 10¹⁷ cm⁻³ while at 28% N₂ the electron density increased to 5.5 × 10¹⁷ cm⁻³. OES

measurements were not performed for the experiments with the addition of O₂ or CO, however, because no change in discharge power was observed at the relatively low concentrations utilized, little to no change is also expected in the plasma properties.

To further investigate the lack of significant change in the plasma gas temperature with N₂ concentration while the electron density increased by almost one order of magnitude, the diameter of the plasma channel was estimated. The flux of electrons (current) through a radial cross-section of the plasma channel was utilized to estimate the diameter, and the volume of the generated plasma channels based on the measured variables was determined by Equation 2 [66].

$$V_p = \frac{I_d L^2}{n_e e \mu_e V_d} \quad \text{E2}$$

I_d : Discharge current, 33 A (no change)

e : Elementary electron charge, 1.602×10^{-19} C (constant)

V_d : Discharge voltage, 9.8 kV@0%, 10.1 kV@28%

L : Gap distance 0.4 cm, (constant)

n_e : Electron density $7.8 \times 10^{16} \text{ cm}^{-3}$ @0%, $5.6 \times 10^{17} \text{ cm}^{-3}$ @28%

$\mu_e(T_p)$: Electron mobility 245 cm²/V/s (no change)

V_p : Plasma channel volume 0.18 mm³ @0%, 0.02 mm³ @28%

I_d and V_d were obtained from electrical measurements and n_e from optical emissions. The electron mobility was determined by solving the Boltzmann equation using BOLSIG+ with the plasma temperatures estimated from OES and an estimation of the reduced electric field for parallel plate geometry (V_d / L) [69]. The length of the plasma channel was assumed to be equal to the electrode gap distance (4 mm).

The plasma volume in pure argon was estimated using E2 to be 0.18 mm³ corresponding to a plasma diameter of 0.24 mm. When 28% N₂ was added to the feed gas, the estimated plasma volume decreased to 0.02 mm³, corresponding to a diameter of 0.08 mm.

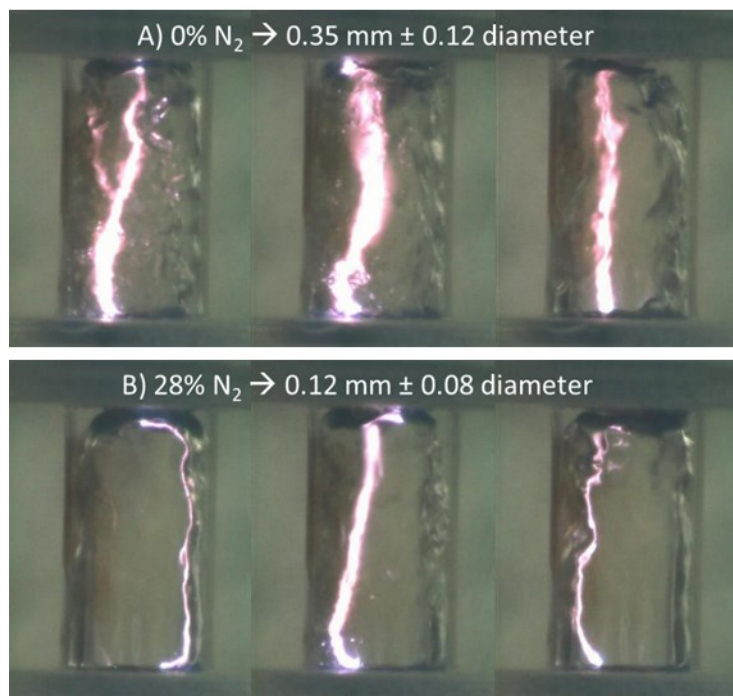


Fig. 4 Various images of a single discharge channel propagating along the gas-liquid interface. Images were taken with a 1/8000 sec shutter speed. Plasma diameter was estimated by the software integrated measurement tool (Keyence, VW-9000). The diameters reported represent the average and standard deviation of the images shown. A) Argon carrier gas, diameter – $0.35 \text{ mm} \pm 0.12$ B) 28% N_2 in argon, diameter – 0.12 ± 0.08 .

The decrease in plasma diameter with increasing N_2 concentration estimated by the current density relation, E_2 , was confirmed by measurements taken with high speed imaging shown in Figure X. Further, the measured values of the plasma diameter found with imaging match well with the current density estimates.

From these estimates of plasma volume and electron density, the total number of free electrons can be calculated as a function of nitrogen concentration. Due to the increase in electron density corresponding with a decrease in plasma volume, the total number of electrons remains relatively unchanged when comparing the pure argon case (1.4×10^{13} total electrons) to 28% N_2 (1.3×10^{13}).

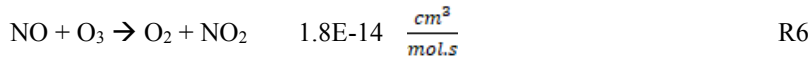
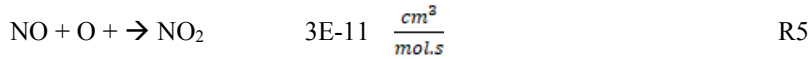
Based on the above assessment of the electrical and plasma properties as well as the photograph shown in Figure 4, the plasma is best described as a filamentary non-thermal plasma channel generated in the gas phase which propagates along the liquid interface [60]. This system is similar to that of a transient spark discharge [70-73]. The plasma generated transient spark discharges are also short-lived filamentary plasma channels (streamers) with an electron density on the same order of magnitude as that found in this study. The energy dissipated per pulse is also similar ($\approx 1 \text{ mJ}$). The transient spark discharge with dry air reports significant NO and NO_2 generation and when a water spray was introduced to the transient spark nitrates and nitrites were also produced. A comparison for NOx generation with transient spark discharges to this work is provided in Table 2.

Potential chemical reactions

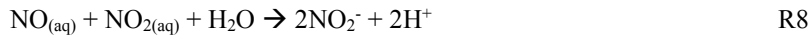
NO formation in thermal plasmas as well as in combustion processes has been well studied where the generally accepted reaction pathway is the Zeldovich mechanism. In this reaction pathway NO is formed through thermal dissociation of O₂ and N₂ where the high bond strength of N₂ causes the N₂ dissociation to be the rate limiting step [1]. NO production from dry air and non-thermal plasma, where the gas temperature is not high enough for thermal dissociation to dominate (<5500 K), is initiated through electron impact dissociation and excitation of O₂ (R2) and N₂ (R1) which generate atomic oxygen and various excited states of N₂. The vibrational excitation of N₂ lowers the bond strength of the molecule and allows for NO generation in non-thermal conditions through reactions with atomic oxygen (R3). Additional NO generation can then also be achieved through Reaction 4.



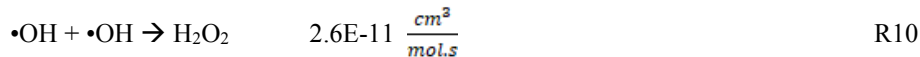
This pathway is known as the Zeldovich mechanism stimulated by vibrational excitation [1]. Further oxidation of NO into NO₂ can then be achieved by additional reactions with atomic oxygen and ozone (R5 and R6).

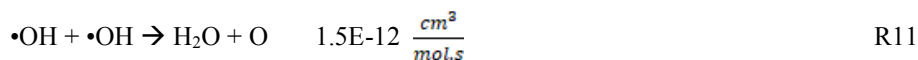


Once formed, the gas phase NO and NO₂ can be converted into NO₂⁻ and NO₃⁻ with the addition of liquid water (R7 and R8). However, solubility of these gasses in water as well as mass transfer resistance limits rapid conversion in this manner.



When water vapor is present in a non-thermal plasma system, •OH is formed in abundance through electron impact with water molecules in the plasma channel (R9). In cases with high •OH concentrations, typically with liquid water contacting the plasma, •OH can combine to form hydrogen peroxide (H₂O₂) (R10) which can then be sequestered in the liquid as a stable product [74]. Alternatively, the •OH can react to form water and atomic oxygen (R11) which could provide an additional source of the atomic oxygen needed for NO production.





An alternate pathway for NO generation when water is present is by the reaction of $\bullet\text{OH}$ with atomic nitrogen (R12). Direct conversion of NO into HNO_2 can also be achieved through reaction with $\bullet\text{OH}$ as well as conversion of NO_2 into HNO_3 (R13 and R14). Due to their high rate constants, Reactions 13 and 14 likely play key roles in the generation of water-soluble nitrogen oxides when water is present in non-thermal plasmas. This is analogous to hydrogen peroxide generation where once the product is sequestered into the liquid it is less likely to be degraded by the plasma.



Gas phase analysis

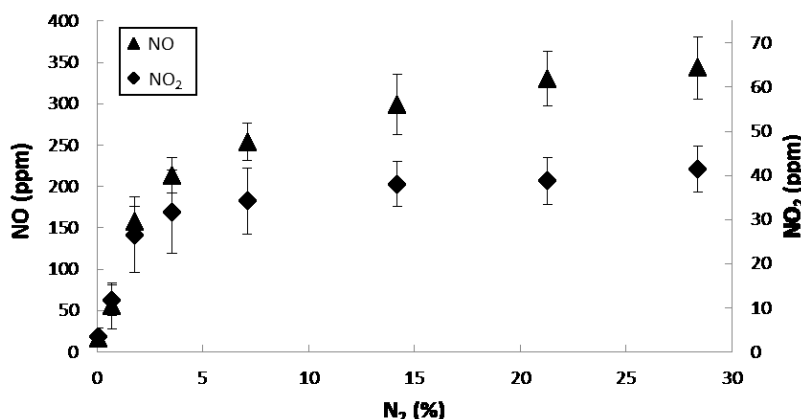


Fig. 5 Gas phase analysis for various N₂/Ar concentrations

Figure 5 shows the concentrations of NO and NO₂ in the gas effluent of the reactor for various N₂/Ar concentrations. Both NO and NO₂ production increase sharply with nitrogen concentration up to 5%. At higher concentrations, NO₂ production levels off while NO production shows a gradual increase. Significantly less NO₂ is produced compared to NO at all N₂/Ar concentrations investigated. This could be explained by NO₂ being a secondary reaction product, NO must first be formed through Reaction 3 followed by an additional reaction with atomic oxygen (R5) to form NO₂. Another consideration is that the reaction rate of O with N₂* to form NO (R3) is faster than that of O with NO to form NO₂ (R5). The leveling off of NO₂ implies that there is an atomic oxygen limitation at higher N₂ concentrations. The leveling off of NO also suggests a limitation on the availability of atomic oxygen, although another possibility is a limitation in $\bullet\text{OH}$ since NO can be directly formed from $\bullet\text{OH}$ and N

(R12). Because no O₂ was present in the feed for these experiments a likely source of atomic oxygen is from water via Reaction 11, this is supported by modeling work with underwater discharges [75, 76]. Reactions 15 and 16 are also potential pathways for O production from water by direct electron collisions and electronically excited water, H₂O*, respectively.



While no chemical probes for atomic oxygen were employed in this study, confirmation of the presence of this short-lived species was found with optical emission spectroscopy (777 nm). A sample spectrum showing the presence of this band is given in the Appendix (Figure 17). Further experimental and modeling studies are needed to assess the most predominant pathway(s) for O production in this system.

Liquid phase analysis

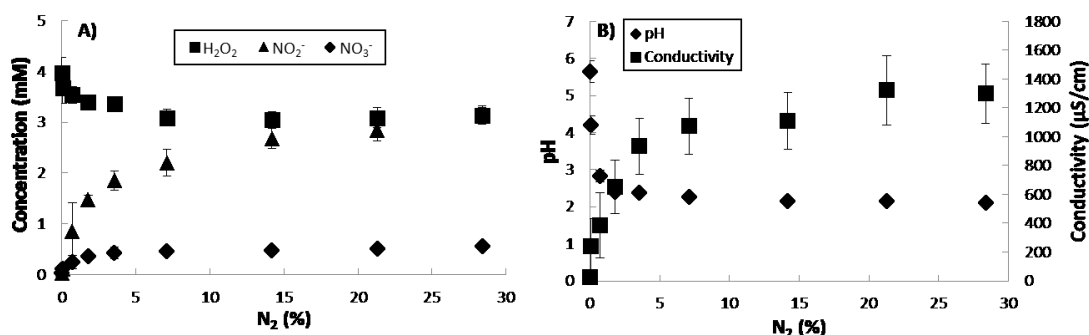


Fig. 6 Liquid phase analysis for various N₂/Ar concentrations. A) – Concentrations of stable chemical species produced B) – pH and conductivity of effluent

Figure 6 shows the liquid phase products for the various N₂/Ar mixtures. For pure Ar the only stable product found in the liquid phase was H₂O₂ [74]. When only a small amount of N₂ was added (550 ppm) NO₂⁻ and NO₃⁻ were detected in the liquid. As the N₂ concentration increased, the NO₂⁻ and NO₃⁻ in the liquid phase increased following the same trends as NO and NO₂ in the gas phase, respectively. This implies that the NO₂⁻ and NO₃⁻ measured at the exit of the reactor are formed directly from the reactions of •OH with gas phase NO and NO₂ (R13 and R14). The decrease in H₂O₂ with increasing N₂ also supports this hypothesis due to •OH radical scavenging by NO and NO₂ in the gas phase. Here, the drop in H₂O₂ cannot be attributed to post plasma reactions with NO₂⁻ because the NO₂⁻ was removed with sodium azide immediately after exiting the reactor. Additional support can also be seen in the significant drop of pH in the liquid effluent as the NO₂⁻ and NO₃⁻ concentrations increase. For these reasons the NO₂⁻ and NO₃⁻ detected in the liquid are assumed to be in the form of HNO₂ and HNO₃. The

simultaneous increase of conductivity and decrease in pH can be correlated to increases of HNO_3 and HNO_2 as shown in Figure 7.

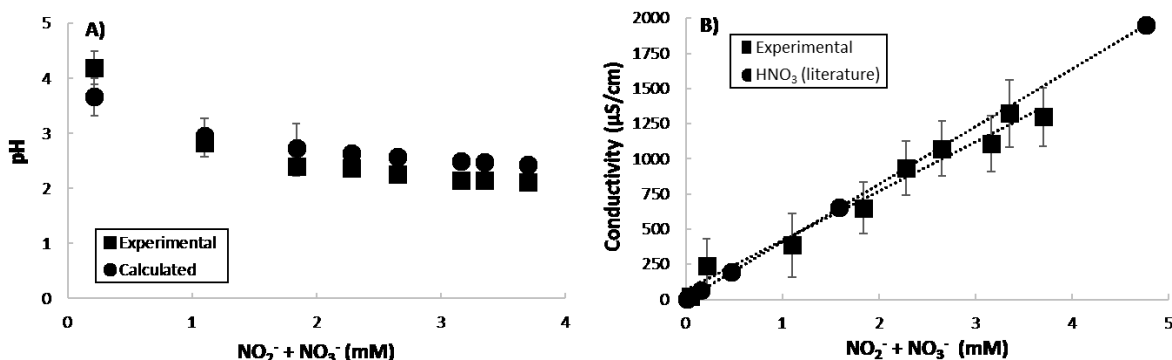


Fig. 7 A) – Comparison of the measured pH of the PAW effluent as a function of nitrite and nitrate concentrations against the calculated pH if it is assumed all NO_2^- and NO_3^- are in the form of HNO_2 and HNO_3 . B) - Comparison of the measured conductivity of the PAW effluent as a function of nitrite plus nitrate concentrations against literature values for the conductivity of various HNO_3 solutions [77].

It should again be noted that if the liquid phase was not quenched at the exit of the reactor, more NO_3^- would be formed in post plasma reactions between NO_2^- and H_2O_2 through the peroxyxynitrite pathway where after a sufficient period of time all NO_2^- would be converted into NO_3^- . Because the peroxyxynitrite pathway occurs on the time scale of minutes to hours depending on the concentration and pH of the plasma activated water, and the average liquid residence time in the reactor is only 127 ms, this pathway can be considered to have a negligible effect on the reactions occurring in the plasma reactor assessed in the present study [58].

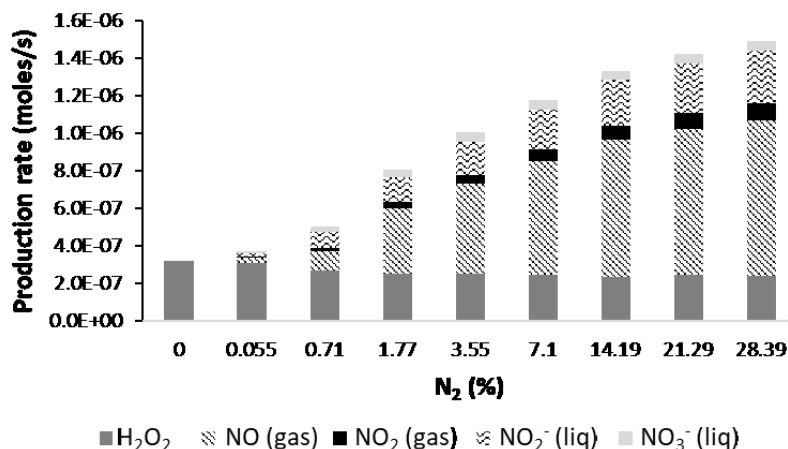


Fig. 8 Production rates of all measured species in the liquid and gas phases as a function of N₂ percentage in feed gas.

Figure 8 shows the rates of production of all the major chemical species produced in the N₂/Ar mixtures. Most nitrogen products detected exist in the gas phase and account for over 80% of all nitrogen oxide species, the majority of which are in the form of NO. High concentrations of H₂O₂ are also produced despite the likelihood that a limitation in •OH is responsible for the lack of conversation of NO and NO₂ into HNO₂ and HNO₃, respectively. This result is consistent with previous analysis of this reactor system that utilized gas and liquid phase radical scavengers to show that H₂O₂ was generated from •OH near the gas-liquid interface and that H₂O₂ was not strongly affected by •OH scavenging in the gas phase [78].

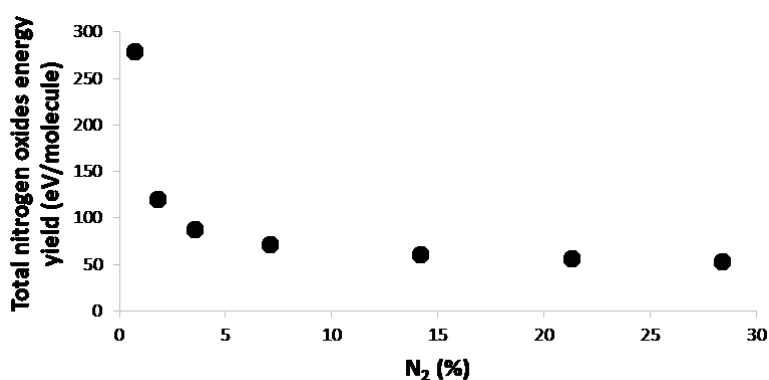


Fig. 9 Energy yield for total nitrogen oxides produced in both the liquid and gas phases as a function N₂/Ar concentration.

The energy yield for total nitrogen oxides produced is shown in Figure 9 as a function of N₂ concentration. From Figure 9 the energy cost per molecule decreases as the N₂ concentration increased up to 10% after which it levels off at approximately 50 eV/molecule. Table 2 provides a comparison of the energy yield of this study to other plasma processes.

Table 2 Energy yield comparison for other plasma systems

Process	Product	Feed	Conditions	Energy yield Moles/J	Energy yield eV/molecule	Reference
Birkeland and Eyde	NO	N ₂ , O ₂	thermal plasma arc	4.1E-07	2.5E+01	cited in [1]
Birkeland and Eyde	NO	N ₂ , O ₂	thermal plasma arc	5.6E-07	1.9E+01	cited in [79]
Birkeland and Eyde	NO	N ₂ , O ₂	thermal plasma arc	8.7E-07	1.2E+01	cited in [80]
Thermal plasma	NO	N ₂ , O ₂	20-30 atm, 3000-3500 K	1.2E-06	9.0E+00	cited in 1 [1]
Microwave	NO	N ₂ , O ₂	magnetic field	3.5E-06	3.0E+00	cited in 1 [1]

non thermal plasma			and cooled walls			
Low pressure	NO	N ₂ , O ₂	with catalyst	1.2E-06	8.7E+00	Mutel, cited in [81]
Plasma jet	NO	N ₂ , O ₂	varied O ₂ /N ₂ ratio	4.6E-07	2.3E+01	Krop/Pollo, cited in [81]
Plasma jet	NO	air	3.5 W plasma jet	9.5E-10	1.1E+04	[82]
Rotating disk with injected water	NO	air		3.1E-07	3.3E+01	Krop/Pollo, cited in [81]
Plasma beam	NO	air	30 kW	1.0E-06	1.0E+01	Alekseev, cited in [81]
Jet arc	NO			2.8E-07	3.7E+01	Coudert, cited in [81]
Plasmatron gliding arc	NO ₃ ⁻	air with water	240 W	3.4E-09	3.1E+03	[83]
Glow discharge	NO ₃ ⁻		420 W 162 MHz	1.8E-09	5.7E+03	[79]
AC gliding arc over water	NO ₃ ⁻	air with water	2 electrodes 300 W	2.9E-08	3.6E+02	[44]
AC gliding arc over water	NO ₃ ⁻	air with water	3 electrodes 600 W	2.4E-08	4.3E+02	[44]
AC gliding arc with spray	NO ₃ ⁻	air with water	3 electrodes 600 W with spray	5.3E-09	2.0E+03	[44]
Bubbling in water	HNO ₃	air with water	underwater pulsed discharge with bubbles	5.4E-09	1.9E+03	[44]
Transient spark	NO _x	Dry air	Transient spark, DC self-pulsing	1.2E-7	9.0E+1	[70]
Transient spark	NO _x , NO ₂ ⁻ , NO ₃ ⁻	air with water	Transient spark with electrospray	1.1E-7	9.6E+1	[73]

The formation of nitric oxide, NO, is a long studied reaction in plasma chemistry due to its importance in fertilizer formation. For example, in 1900 Birkeland and Eyde developed a thermal plasma arc furnace which was used commercially to make NO from N₂ and O₂. The thermodynamic limit for this reaction is 1 eV/molecule and the efficiency reported by Birkeland and Eyde was 25 eV/molecule [1]. The highest efficiency for nitrogen fixation with a plasma process was a non-thermal microwave plasma with magnetic field and low pressure (3 eV/mol) however, the cost of attaining the low pressure and the magnetic field were not included [1]. Of the various plasma process listed in Table 2 the transient spark [70-72] has the most closely related plasma properties to this work and the energy yield for total NO_x (NO/NO₂) from air is similar in magnitude to that reported in this study. When an electrospray was combined with the transient spark, nitrate and nitrite were observed in the exiting liquid, however the energy yield for total nitrogen oxides remained similar [73]. It is important to note that the plasma reactor utilized in this work only requires air and water feed and operates at near atmospheric conditions.

•OH scavenger

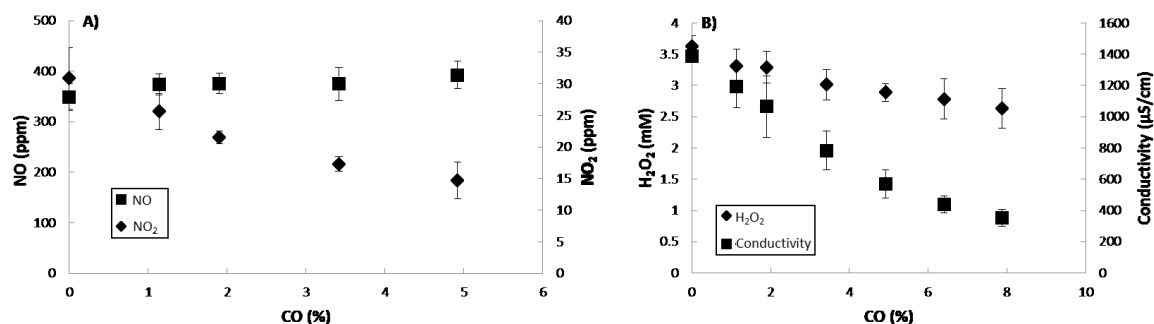
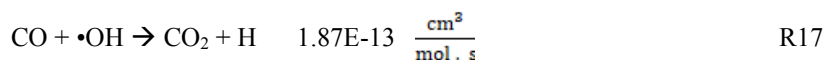


Fig. 10 Chemical analysis of the gas phase (left) and liquid phase (right) for various concentrations of carbon monoxide added to a 28% N₂/Ar mixture. Conductivity was used as an indicator of changes in NO₂⁻ and NO₃⁻ in the liquid phase.

To further investigate the role of •OH in the process, CO was added to the gas phase (0-5%) of the 28% N₂/Ar mixture. CO is an excellent gas phase •OH scavenger and due to the fast rate of reaction between •OH and CO (R15), CO added to the gas phase will rapidly react with •OH radicals and prevent them from participating in reactions with other compounds [78, 84]. The effectiveness of CO as a gas phase •OH scavenger is illustrated in Figure 10 where the •OH consumed in CO₂ production by Reaction 17 increases with CO% added to the gas feed.



For the data shown in Figure 10, conductivity was used as an indicator of changes in NO₂⁻ and NO₃⁻ in the liquid phase. The addition of CO decreased the production of NO₂, NO₂⁻, NO₃⁻, and H₂O₂ significantly but had little effect on NO. This result clearly indicates that direct •OH reactions play important roles in NO₂, NO₂⁻, and NO₃⁻ generation, and may not directly react with N via Reaction 12 to a significant degree. With no O₂ present in the feed gas, a reduction in the •OH concentration will also cause a reduction in the atomic oxygen formed by Reaction 11. Because there are no possible reactions of •OH to form NO₂, the reduction in NO₂ formation is likely caused by the reduction in availability of atomic oxygen. However, a chemical probe specific to atomic oxygen would be useful to confirm this finding. Since reactions with atomic oxygen are also probable pathways for NO generation, the lack of any significant change in NO concentration is possibly due to a decrease in NO production (R3) being balanced by a decrease in consumption (conversion to NO₂), (R5).

The lower limit on the production of •OH when no N₂ was present in the feed can be estimated based on the conversion of CO to CO₂ (R17) and H₂O₂ formation (R10). Based on these reactions, for every mole of CO₂ produced one mole of •OH is consumed while for every mole of H₂O₂ produced two moles of •OH are consumed. Additionally, the •OH consumed in the generation of nitrogen oxides was estimated by assuming that all NO and NO₂ are produced by reactions with atomic oxygen (R3 and R5) and that the atomic oxygen is produced by Reaction

11. Thus, for every mole of NO produced two moles of $\bullet\text{OH}$ are consumed, and for NO_2 four moles of $\bullet\text{OH}$ are consumed. If the NO_2^- are NO_3^- are assumed to be produced from reaction of $\bullet\text{OH}$ with NO and NO_2 (R13 and R14), production of NO_2^- equates to three $\bullet\text{OH}$ consumed while NO_3^- equates to five $\bullet\text{OH}$. This information is summarized in the Table 3.

Table 3 Assumed hydroxyl radical consumption based on production of measured products

Reaction	$\bullet\text{OH}$ utilized per mole produced
R10	$\text{H}_2\text{O}_2 = 2\text{OH}$
R17	$\text{CO}_2 = 1\text{OH}$
R11	$\text{O} = 2\text{OH}$
R3	$\text{NO} = 2\text{OH}$
R5	$\text{NO}_2 = 4\text{OH}$
R13	$\text{HNO}_2 = 3\text{OH}$
R14	$\text{HNO}_3 = 5\text{OH}$

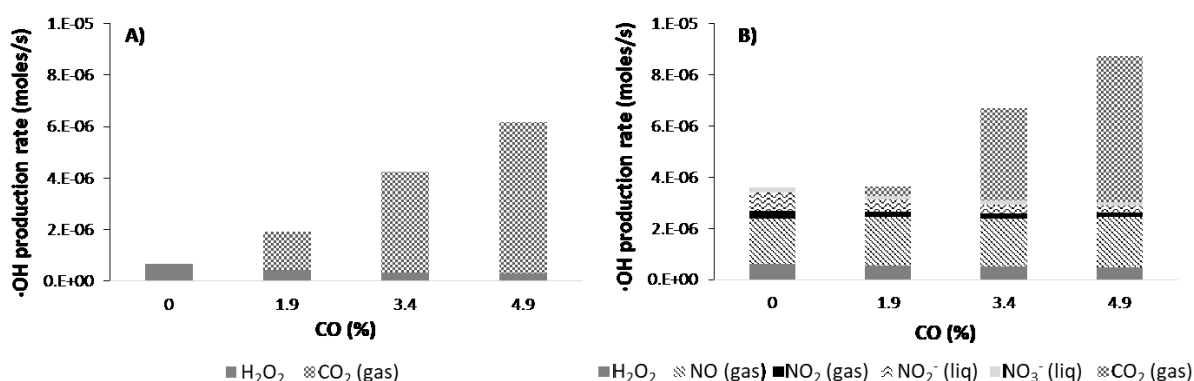


Fig. 11 Estimated hydroxyl radical production rate based on the generation of H_2O_2 , CO_2 , and nitrogen oxides for various gas mixtures. A) – Ar/CO, B) – 28% N_2 /Ar/CO

The production rates of $\bullet\text{OH}$ based on the assumptions in Table 3 are shown in Figure 11. Figure 11a shows the $\bullet\text{OH}$ production rate when only argon was used as the carrier gas with various concentrations of CO added. As the concentration of CO was increased the measured $\bullet\text{OH}$ production rate increased significantly while the production rate of H_2O_2 slightly decreased as a result of the $\bullet\text{OH}$ scavenging by CO. At 3.4% CO the $\bullet\text{OH}$ production rate was 4×10^{-6} moles/s. These results are similar to experiments performed in the same reactor but utilizing a different power supply based upon microsecond pulses where an $\bullet\text{OH}$ production rate of 5×10^{-7} moles/s

was found at 2.6% CO [78]. Based on the high production rate of $\bullet\text{OH}$ from CO_2 measurements it is clear that significantly more $\bullet\text{OH}$ is produced in the system than can be accounted for by H_2O_2 .

Figure 11b shows the $\bullet\text{OH}$ production rate for the 28% N_2/Ar mixture with various concentrations of CO. The $\bullet\text{OH}$ production rate was lower in the case with 1.9% CO in Ar than in the case with 0% CO with 28% N_2 due to the contribution of $\bullet\text{OH}$ scavenged by nitrogen oxides. As the CO concentration was increased, $\bullet\text{OH}$ production continued to increase up to a value of 8.3×10^{-6} moles/s. This result shows that even with the $\bullet\text{OH}$ accounted for in the production of nitrogen oxides and H_2O_2 there is still a significant amount of $\bullet\text{OH}$ that remains unutilized (available to react with CO). The energy yield for $\bullet\text{OH}$ production can also be calculated by dividing the production rate by the corresponding average discharge power. The highest energy yield was found to be 7×10^{-7} moles/J for the case of 28% $\text{N}_2/4.9\%$ CO in balance Ar and this value is in close agreement with the value of 5×10^{-7} moles/J found in the previous work with microsecond pulses and 2.6% CO in Ar in same reactor [78]. This result suggests that the energy yield in a nanosecond discharge is not significantly different than that of a microsecond discharge; however, it can be noted that there are other advantages of the nanosecond power supply, including tolerance of high solution conductivity [63].

Oxygen addition

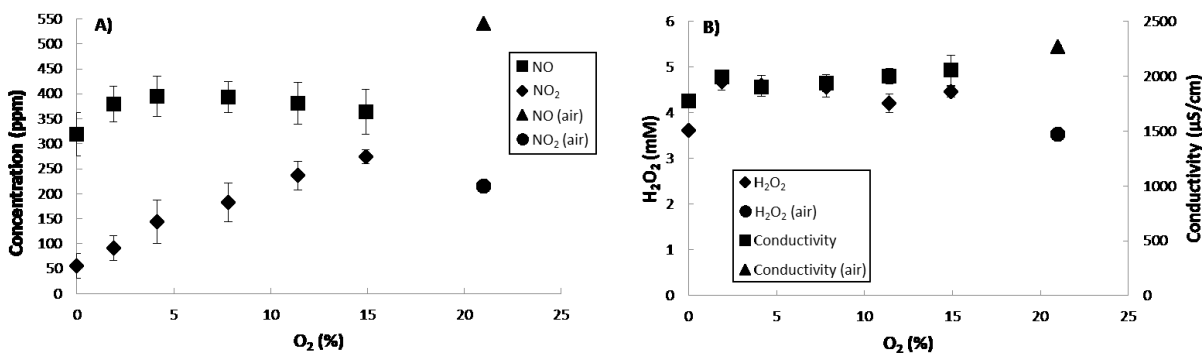


Fig. 12 Chemical analysis of the gas phase (A) and liquid phase (B) for various concentrations of oxygen added to a 28% nitrogen mixture with balance argon. Experimental results for air are also displayed.

To further investigate the role of reactive oxygen species in the process, various concentrations of O_2 (0-15%) were added to the 28% N_2/Ar mixture. An additional experiment was performed with air. Results for the gas and liquid phase analyses are shown in Figure 12. The only significant change measured with the addition of O_2 was a large increase in NO_2 generation. Because NO is a precursor for NO_2 , it is likely that NO production also increased but it was rapidly converted to NO_2 due to an increased concentration of reactive oxygen species. This would explain the lack of any net change in NO as O_2 concentration was increased. The lack of an increase in conductivity implies that the NO_2^- and NO_3^- concentrations did not change with added O_2 and provides further evidence that the conversion of NO and NO_2 into these products is limited by $\bullet\text{OH}$ (R13 and R14) and not by other reactive oxygen species.

When air was utilized the results were similar to those with the 15% O₂, 28% N₂, balance Ar mixture. Higher concentrations of NO and NO₂ were observed in the gas phase compared to the case with no O₂; however, little increase was seen in the production of NO₂⁻ and NO₃⁻. This result is again consistent with higher atomic oxygen concentrations leading to an increase in NO and NO₂ generation and with a limitation of •OH for further conversion of these products to HNO₂ and HNO₃. It should also be noted that no O₃ was detected in the gas phase with FTIR for both the O₂ addition and air experiments. This is consistent with other studies with similar plasma conditions where the lack of ozone was attributed to plasma (gas) temperatures above ambient leading to rapid thermal degradation of O₃ [71, 85, 86]. Additionally, any O₃ which could be formed would rapidly react with NO (R6) [26, 27].

CONCLUSIONS

Chemical analysis of the products generated when filamentary non-thermal plasma channels propagate along a flowing liquid water film in N₂/Ar atmosphere shows significant amounts of NO and NO₂ in the gas phase and NO₂⁻, NO₃⁻, and H₂O₂ in the liquid. By inducing chemical quenching of the liquid effluent, this work decouples the chemical reactions induced by the plasma from those which occur in the post-plasma solution. This allows for assessment of the reaction pathways leading to the generation of these chemical species without the complications induced by secondary interactions of the plasma generated molecules. Current work is in progress to develop chemical reaction modeling for further assessment of the reaction pathways described in this paper.

In this work the gas temperature of the plasma channel was found to be approximately 525 K and was unaffected by the N₂ concentration. The electron density was $7.8 \times 10^{16} \text{ cm}^{-3}$ with no N₂ present (pure Ar) and increased to $5.6 \times 10^{17} \text{ cm}^{-3}$ at 28% N₂ in Ar. In contrast, the volume (diameter) of the plasma channel decreased with increasing N₂ resulting in a negligible change in total free electrons with N₂ concentration. The production of all nitrogen oxides increased as a function of the amount of N₂ in the feed gas giving a maximum production rate of $1.5 \times 10^{-6} \text{ moles/s}$ at an energy yield of 50 eV/molecule at the highest N₂ concentration investigated (28%). The negligible change in total free electrons with N₂ implies that the significant increase in total nitrogen oxides produced with N₂ was mainly caused by an increased availability of nitrogen and not by an increase of free electrons available for reaction.

This work shows that significant generation of nitrogen oxides is possible without a source of oxygen in the feed gas. The reaction of •OH to form water and O (R11) is one likely source of the atomic oxygen needed for NO and NO₂ generation, however, other reactions are possible (R15 and R16). NO formation can then proceed through Reaction 3. However, the addition of oxygen to the gas feed did enhance the overall NO_x production by adding an additional atomic oxygen source (R2). •OH does not otherwise appear to directly affect the generation of NO (R12) or NO₂ but does play a key role in the conversion of NO and NO₂ into HNO₂ and HNO₃, respectively. While further conversion of the remaining gas phase NO and NO₂ into HNO₂ and HNO₃ appears to be limited by •OH, there is still a significant quantity of •OH unutilized as evident from CO scavenging (CO₂ production) and H₂O₂ production. Future work should be done to investigate capitalizing on this unutilized •OH.

ACKNOWLEDGEMENTS

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APPENDIX

Electrical measurements

Temporal alignment of current and voltage probes is essential for accurate analysis of nanosecond discharges. For temporal alignment of these probes the nanopulser was discharged across a resistor placed inside the Rogowski coil while the two voltage probes measured the electrical potential across the resistor. The deskew of each voltage probe was then adjusted to ensure simultaneous rise in each voltage probe with current.

For analysis of the plasma discharge, the high voltage probes were connected across the stainless-steel inlet and outlet capillaries to measure the electric potential across the plasma discharge region. The reactor was placed inside the Rogowski coil so that the discharge region was centered within the coil to measure current flow through the discharge region only. With placement of the voltage and current probes in this fashion, the measured values give the electrical potential between the electrodes and current flow only within the formed plasma channels. More details of the electrical analysis can be found in our previous work [60, 62].

H₂O₂ quantification

For H₂O₂ quantification the effluent was discharged directly into a sodium azide solution of sufficient quantity to rapidly remove all NO₂⁻ from the liquid phase. 2 mL of effluent from reactor was discharged into a 1 M sodium azide solution at an equal 1 to 1 volume ratio (i.e. 2 mL sodium azide + 2mL effluent). The H₂O₂ in the resulting solution was then quantified with the TiSO₄ colorimetric method using a UV-Vis spectrometer detailed in our previous publications as well as others (PerkinElmer, Lambda 35) [58, 61, 87]. The resulting concentration was then multiplied by a factor of 2 in order to account for the dilution with the sodium azide solution.

Nitrate and nitrite quantification

For nitrate and nitrite quantification the pH of the effluent must be rapidly increased to slow/stop the reaction of NO₂⁻ with H₂O₂. In addition, the solutions were diluted to approximately 10 ppm total nitrogen for protection of the IC instrument. For this procedure, 3 mL of effluent was directly discharged into a 26.7 mL solution of 1 mM NaOH. The pH of the resulting mixture after effluent addition was approximately 10. Calibration curves for the IC were prepared using various dilutions of NaNO₂ and KNO₃. All samples were analyzed on a Dionex, Aquion ion chromatograph equipped with an IonPac™ AS22 column (4 × 250 mm), an AERS™ 500 carbonate suppressor, and a conductivity detector. The eluent was 4.5 mM sodium carbonate mixed with 1,4 mM sodium bicarbonate and supplied to the IC system at an isocratic flow of 1.2 mL/min. A sample IC spectrum is shown in Figure 13.

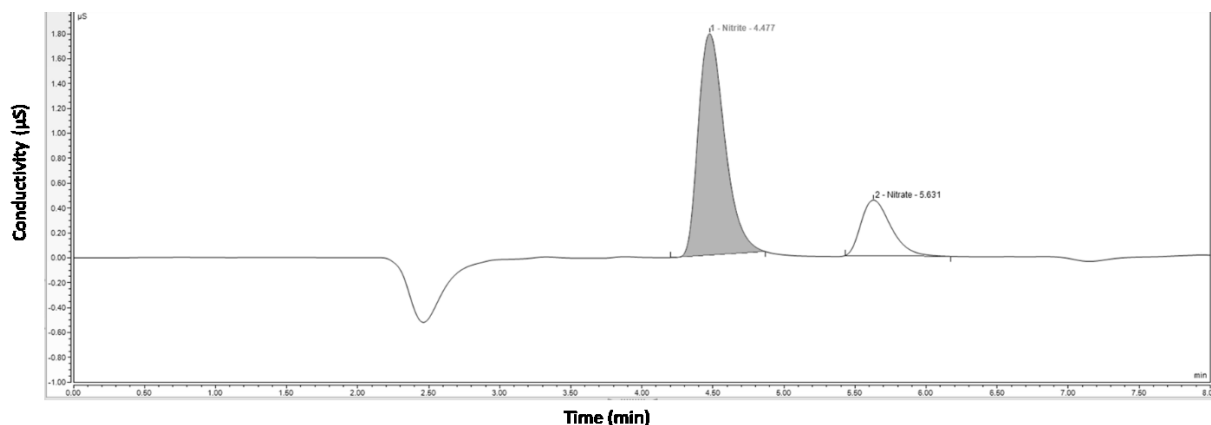


Fig. 13 Sample IC spectrum for 28% N₂ with balance argon as the carrier gas

NO and NO₂ quantification

An FTIR (Jasco – 6700) equipped with a gas flow cell was utilized to analyze the gas phase effluent. Calibration curves for NO and NO₂ were generated by flowing dilutions of 1000 ppm gas standards generated with a mass flow controller (Brooks, 5850E) and balanced with N₂ at the same total flow rate as the experimental conditions (3.4 L/min). For NO the band at 1917.86 cm⁻¹ was used for quantification while for NO₂ the band at 1637.78 cm⁻¹ was utilized. The following instrument conditions were used for all FTIR measurements: 8 accumulations, 0.25 cm⁻¹ resolution, 32 gain, 1.8 mm aperture, and 2 mm/sec scanning speed. Prior to measurements the gas flow cell was purged with N₂ to remove water and air. All measurements were taken after a steady state in the flow cell had been reached by ensuring no change in the intensity of the bands for a period of two minutes. Sample experimental FTIR spectra are shown in Figures 14 and 15.

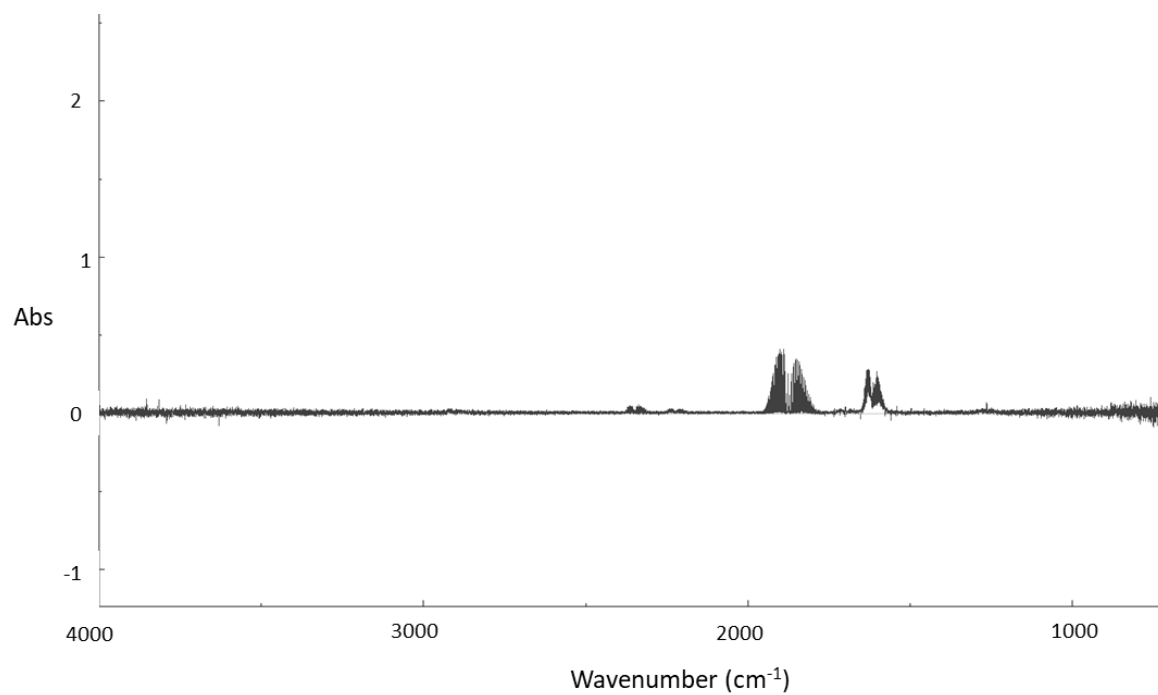


Fig. 14 Sample FTIR spectrum for 28% N₂ with balance Ar as the carrier gas

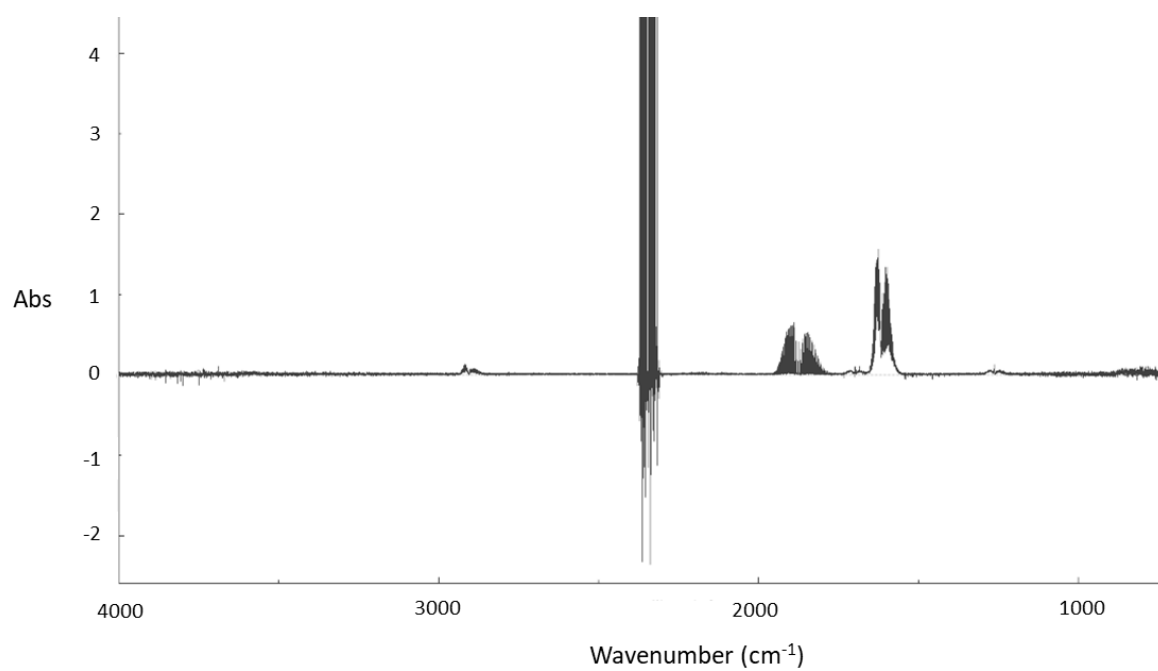


Fig. 15 Sample FTIR spectrum for air as the carrier gas

Optical Emission Spectroscopy

For OES measurements the probe tip was oriented towards the center of the discharge region in as close proximity as possible to the quartz reactor body (approx. 5mm). Stark broadening of the H_{α} peak was utilized for estimation of the electron density. The H_{α} peak was observed using an optical emission microscope (Avantes, AvaSpec-ULS3848; wavelength range: 600-700 nm) at 656.3 nm. The H_{α} peak was deconvoluted into two Voigt profile. The Voigt profile was then deconvoluted into Gaussian and Lorentz profiles. The FWHM of Gaussian profile was determined by Doppler and instrument broadening where Doppler broadening was obtained using gas temperature, and instrumental broadening was obtained by calculating the FWHM of the spectral line with the optical fiber connected to a mercury-argon lamp (Avalight-CAL). The FWHM of the Stark broadening was calculated from the relationship between the FWHM of the Van der Waal's broadening and the FWHM of the Lorentzian profile. More details of this method can be found in a previous publication and a sample of the peak fitting can be found in Figure 16 [63].

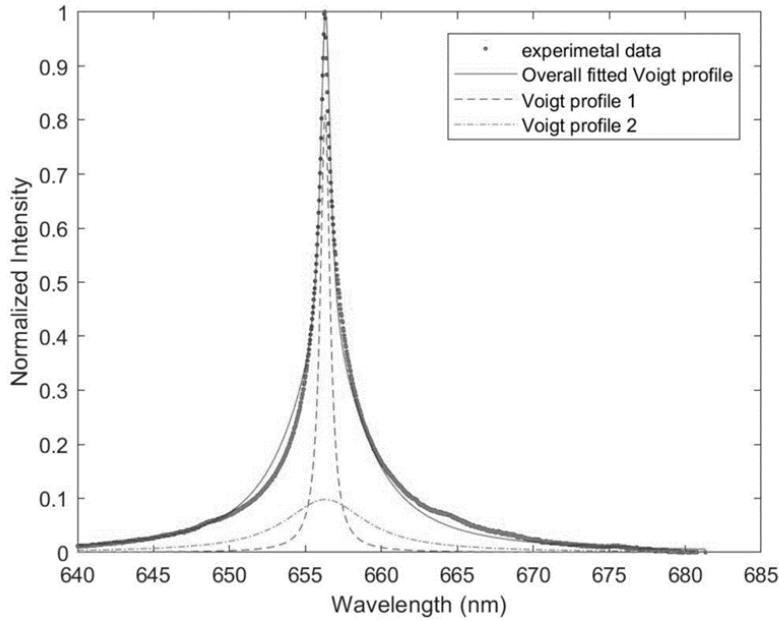


Fig. 16 H_{α} peak fitting in argon discharge by two Voigt profile for 28% N_2 in argon.

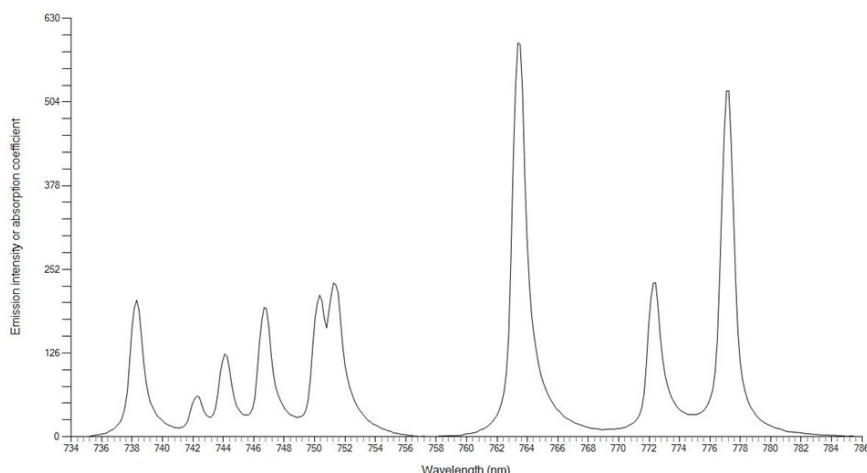


Fig. 17 Optical emission spectra for 28% nitrogen in argon showing a band at 777 nm which indicates presence of atomic oxygen

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